

[PIXEL STRUCTURE AND MANUFACTURING METHOD THEREOF]

Abstract

A pixel structure and fabricating method thereof is provided. The pixel structure includes a scan line, a data line, an active component, a plurality of transparent capacitance electrodes and a pixel electrode. First, an active component, a scan line and a data line are formed over a substrate, wherein the active component is electrically connected to the scan line and the data line. In addition, a plurality of transparent capacitance electrodes are formed over the substrate. Next, a pixel electrode is formed over the transparent capacitance electrode and electrically connected to the active component. Thus, the pixel electrode and the transparent capacitance electrodes constitute a multilayer pixel storage capacitor. Since the pixel storage capacitor is comprised of transparent material, and being a multilayer structure, the capacitance of the pixel storage capacitor and the aperture ratio of the pixel structure respectively are increased.